

	Type	Hits	Search Text	DBs
1	BRS	48354	(isolation dielectric) adj (material materials)	USPAT
2	BRS	3367	(halide fluorine fl chloride cl idomine i) near2 (dope doped doping)	USPAT
3	BRS	223	(halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide)))	USPAT
4	BRS	107	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 (dope doped doping))	USPAT
5	BRS	32	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide))))	USPAT
6	BRS	8809	(isolation dielectric) near2 trench	USPAT
7	BRS	14	((halide fluorine fl chloride cl idomine i) near2 (dope doped doping)) same ((isolation dielectric) near2 trench)	USPAT
8	BRS	2	((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide)))) same ((isolation dielectric) near2 trench)	USPAT
9	IS&R	1770	(257/506,507,508,509,510,513,752).CCLS.	USPAT
10	IS&R	1789	(438/218,219,221,424,427,435,789,790).CCLS.	USPAT
11	BRS	760	((257/506,507,508,509,510,513,752).CCLS.) and trench	USPAT
12	BRS	1242	((438/218,219,221,424,427,435,789,790).CCLS.) and trench	USPAT
13	BRS	30650	(isolation dielectric) adj (material materials)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
14	BRS	2877	(halide fluorine fl chloride cl idomine i) near2 (dope doped doping)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
15	BRS	146	(halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide)))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
16	BRS	90	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 (dope doped doping))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
17	BRS	34	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide))))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
18	BRS	9101	(isolation dielectric) near2 trench	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
19	BRS	8	((isolation dielectric) near2 trench) same ((halide fluorine fl chloride cl idomine i) near2 (dope doped doping))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
20	BRS	0	((isolation dielectric) near2 trench) same ((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide))))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Type	Hits	Search Text	DBs
21	BRS	51	(low adj k low-k) near2 (trench trenches)	USPAT
22	BRS	39	(low adj k low-k) near2 (trench trenches)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
23	BRS	12	("3515585" "3700497" "3766438" "3796613" "3846166" "3961355" "3985597" "4160991" "4164458" "4333794" "4367119" "4502914").PN.	USPAT
24	BRS	138	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 (dope doped doping))	USPAT
25	BRS	18	((halide fluorine fl chloride cl idomine i) near2 (dope doped doping)) same ((isolation dielectric) near2 trench)	USPAT
26	BRS	41	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide))))	USPAT
27	BRS	2	((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide)))) same ((isolation dielectric) near2 trench)	USPAT
28	BRS	825	((257/506,507,508,509,510,513,752).CCLS.) and trench	USPAT
29	BRS	1365	((438/218,219,221,424,427,435,789,790).CCLS.) and trench	USPAT
30	BRS	120	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 (dope doped doping))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
31	BRS	44	((isolation dielectric) adj (material materials)) same ((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide))))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
32	BRS	10	((isolation dielectric) near2 trench) same ((halide fluorine fl chloride cl idomine i) near2 (dope doped doping))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
33	BRS	0	((isolation dielectric) near2 trench) same ((halide fluorine fl chloride cl idomine i) near2 ((dope doped doping) near2 (silicon adj (dioxide oxide))))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
34	BRS	63	(low adj k low-k) near2 (trench trenches)	USPAT
35	BRS	61	(low adj k low-k) near2 (trench trenches)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
36	IS&R	2	((("5459096") or ("5429995"))).PN.	USPAT
37	BRS	7	("5780346" "6114216" "6348389" "6350662" "6368931" "6410403" "6509271").PN.	USPAT
38	BRS	5	("5567660" "6187663" "6294832" "6492257" "6521524").PN.	USPAT